

L Number	Hits	Search Text	DB	Time stamp
16	132	ZAMPINI-A ZAMPINI-ANTHONY	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:08
17	72894	acetal ketal	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:09
18	18	((ZAMPINI-A ZAMPINI-ANTHONY) and (acetal ketal))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:09
19	8	((ZAMPINI-A ZAMPINI-ANTHONY) and (acetal ketal)) and ((acid photoacid) adj labile)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:36
20	1322	(acetal ketal) and ((acid photoacid) adj labile)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:13
21	428	((acetal ketal) and ((acid photoacid) adj labile)) and (430/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:14
22	281	((fluorinated fluorine fluoro) and (((acetal ketal) and ((acid photoacid) adj labile)) and (430/\$.ccls.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:26
23	3620	disulfide same oxygen	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:27
24	312	(disulfide same oxygen) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:46
25	14	((disulfide same oxygen) and (resist photoresist)) and ((acid photoacid) adj labile)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:45
26	160	(disulfide adj compound) same (oxygen)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:56
27	0	((disulfide adj compound) same (oxygen)) and ((acid photoacid) adj labile)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 11:45
28	53	((disulfide adj compound) same (oxygen)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:37
29	11	(disulfide adj compound) and (resist photoresist) and ((acid photoacid) adj labile)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:36
30	312	2-mercaptothiazole	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:36

31	9	2-mercaptothiazole and ((acid photoacid) adj labile)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:36
32	14	2-mercaptothiazole and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:37
33	14	(2-mercaptothiazole and (resist photoresist)) not (2-mercaptothiazole and ((acid photoacid) adj labile))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:40
34	6014	(photoacid acid) adj labile	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:41
35	1167	alicyclic admantyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:41
36	36775	alicyclic adamantyl norbornyl norbornene adamantane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:41
37	5	2-mercaptothiazole and ((photoacid acid) adj labile) and (alicyclic adamantyl norbornyl norbornene adamantane)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:42
38	6029	(organic adj solvent) and (basic adj compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:42
39	293861	surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:42
40	1311	dissolution adj inhibitor	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:43
41	1876	(thiol disulfide thiolsulfonate) adj derivative	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:43
42	450751	resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:43
43	1797737	resin	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:43
44	9	(resin (resist photoresist)) and ((thiol disulfide thiolsulfonate) adj derivative) and ((organic adj solvent) and (basic adj compound))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:48
45	37	((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:51
46	47	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and ((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant) and (dissolution adj inhibitor)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 13:07

47	4	saWATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI WATANABE-SATOSHI-C-O-NIPPON-ST WATANABE-SATOSHI-C-O-SPECIALTY WATANABE-SATOSHI-SHIN-ETSU-CHE	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:57
48	1177	WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI WATANABE-SATOSHI-C-O-NIPPON-ST WATANABE-SATOSHI-C-O-SPECIALTY WATANABE-SATOSHI-SHIN-ETSU-CHE	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 13:05
49	2	(WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI WATANABE-SATOSHI-C-O-NIPPON-ST WATANABE-SATOSHI-C-O-SPECIALTY WATANABE-SATOSHI-SHIN-ETSU-CHE) and ((thiol disulfide thiolsulfonate) adj derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 13:05
50	0	2002303986.URPN.	USPAT	2004/07/07 13:05
51	145158	(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 13:09
52	8	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI WATANABE-SATOSHI-C-O-NIPPON-ST WATANABE-SATOSHI-C-O-SPECIALTY WATANABE-SATOSHI-SHIN-ETSU-CHE)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 13:13
53	6	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI WATANABE-SATOSHI-C-O-NIPPON-ST WATANABE-SATOSHI-C-O-SPECIALTY WATANABE-SATOSHI-SHIN-ETSU-CHE)) not (WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI WATANABE-SATOSHI-C-O-NIPPON-ST WATANABE-SATOSHI-C-O-SPECIALTY WATANABE-SATOSHI-SHIN-ETSU-CHE) and ((thiol disulfide thiolsulfonate) adj derivative))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 13:21
-	182614	thiol disulfide thiolsulfonate mercapto\$	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:03
-	2424	ped (post-exposure adj delay) (post adj exposure adj delay)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:18
-	409168	resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 17:00
-	17620	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	22477	(basic adj compound) (nitrogen-containing adj compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	266188	surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	1095	dissolution adj inhibitor	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:00

-	98	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 17:01
-	98	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))) and "11"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 17:01
-	92	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))) and surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 17:01
-	98	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))) and (surfactant (dissolution adj inhibitor) ((basic adj compound) (nitrogen-containing adj compound)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/29 13:23
-	1	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))) and (surfactant (dissolution adj inhibitor) ((basic adj compound) (nitrogen-containing adj compound)))) and ((thiol disulfide thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post adj exposure adj delay)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 17:02
-	4	(thiol disulfide thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post adj exposure adj delay))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 17:06
-	97	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))) and (surfactant (dissolution adj inhibitor) ((basic adj compound) (nitrogen-containing adj compound)))) not ((thiol disulfide thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post adj exposure adj delay)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 17:06
-	126812	\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:44
-	3	(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) same (ped (post-exposure adj delay) (post adj exposure adj delay))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 18:38
-	6888	(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/28 18:40
-	71	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:30
-	30	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant) and (dissolution adj inhibitor)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:51

-	25	((((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant) and (dissolution adj inhibitor)) not (((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound)))) and (surfactant (dissolution adj inhibitor) ((basic adj compound) (nitrogen-containing adj compound)))) not ((thiol disulfide thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post adj exposure adj delay))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/29 13:38
-	2	(ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:28
-	0	(ped (post-exposure adj delay) (post adj exposure adj delay)) near (additive)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:24
-	2430	ped (post-exposure adj delay) (post adj exposure adj delay)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:19
-	2163	(thiol disulfide thiolsulfonate) near derivative	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:43
-	0	((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) not ((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:16
-	1	(ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:19
-	21	(ped (post-exposure adj delay) (post adj exposure adj delay)) and ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:19
-	0	2002303986.URPN.	USPAT	2003/09/03 11:23
-	705	(thiol disulfide thiolsulfonate) near agent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:24
-	10	(ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:24
-	236	(ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:29
-	1	((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:29
-	225	((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	126948	\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:39

-	11	((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:52
-	2	("6099880").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 11:52
-	0	20020136981.URPN.	USPAT	2003/09/03 12:07
-	112931	THIOL DISULFIDE THIOLSULFONATE	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:06
-	7137	(THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:06
-	1564	((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:17
-	121	((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:17
-	15	(US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.	USPAT; US-PGPUB; JPO	2003/09/03 14:26
-	120	(((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:26
-	120	(((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT ((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:01
-	17642	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:27
-	266458	surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:27

-	0	<p>((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))) AND (((acid photoacid) near generat\$4) (photoactive near compound)) AND surfactant</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:27
-	0	<p>((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))) AND (((acid photoacid) near generat\$4) (photoactive near compound))</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:28
-	111	<p>((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))) AND surfactant</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 14:42

-	0	((((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) AND surfactant) AND (430/\$.CCLS.) ("5589312") or ("5344694")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:04
-	5		USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:05
-	2	wo-9306529-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:06
-	7	((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:06
-	8055	(430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:43
-	31	((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:22
-	31	((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:22
-	31	(((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)) not (((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:22

-	30	(((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)) not (((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$.did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$.did. or (JP-2002303986-\$.did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	246076	stabilizer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:51
-	12420	stabilizer and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	17642	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	22496	(basic adj compound) (nitrogen-containing adj compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	266458	surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	1096	dissolution adj inhibitor	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:00
-	42	(stabilizer and (resist photoresist)) and ((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant and (dissolution adj inhibitor)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:00

-	41	((stabilizer and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant and (dissolution adj inhibitor)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:01
-	41	(((stabilizer and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant and (dissolution adj inhibitor)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) not (((((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)) not (((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$.did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$.did. or (JP-2002303986-\$.did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:02
-	855	stabilizer and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:01
-	1	(stabilizer same ((thiol disulfide thiolsulfonate) near derivative)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:53

-	53	stabilizer same ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:54
-	854	(stabilizer and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)) not (stabilizer same ((thiol disulfide thiolsulfonate) near derivative))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:02
-	706	(stabilizer and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)) not (stabilizer same ((thiol disulfide thiolsulfonate) near derivative))	USPAT	2003/09/03 18:02
-	116	stabil\$6 same ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:50
-	4	(stabil\$6 same ((thiol disulfide thiolsulfonate) near derivative)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:51
-	8055	(430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:43
-	2163	(thiol disulfide thiolsulfonate) near derivative	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:50
-	126948	\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:44
-	127073	((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:50
-	10164	stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:50
-	701	(stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 19:55
-	34	((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/07 12:51
-	6896	((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 19:55
-	527	((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 19:55
-	493	((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 19:55

-	233	(((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.))) and (\$5acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 19:59
-	233	((((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.))) and (\$5acid near generat\$3)) not (((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 19:59
-	233	((((((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.))) and (\$5acid near generat\$3)) not (((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.))) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 19:59
-	2	("6406828") or ("6218076").PN.	USPAT; US-PGPUB; EPO; JPO	2004/06/29 13:23
-	2	("20010044070") or ("6395446").PN.	USPAT; US-PGPUB; EPO; JPO	2004/06/29 13:39
-	37	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant) and (dissolution adj inhibitor)) not (((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))) and (surfactant (dissolution adj inhibitor) ((basic adj compound) (nitrogen-containing adj compound)))) not ((thiol disulfide thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post adj exposure adj delay))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/06/29 14:01
-	3	("6280897") or ("4304841") or ("6406828").PN.	USPAT; US-PGPUB; EPO; JPO	2004/07/07 11:08
-	17800	(thiol disulfide thiolsulfonate mercapto\$) adj (compound derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:04
-	450751	photoresist resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:04

-	5152	(photoacid acid) adj generator	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:04
-	1098651	solvent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:04
-	35	((thiol disulfide thiol sulfonate mercapto\$) adj (compound derivative)) and (photoresist resist) and ((photoacid acid) adj generator) and solvent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:08
-	0	jp-5550806-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:09
-	0	jp-55050806-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:09
-	0	jp-550050806-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:09
-	0	jp-5675643-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:09
-	1	jp-56075643-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/06 19:09